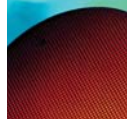




GaSonics L3510 Ashing System Single Wafer

The Gasonics L3510 is a versatile downstream photoresist removal system, designed for clean, damage-free removal of the most difficult resist structures. Utilizing the production-proven L-Series platform, the L3510 has a wide process window due to its patented microwave plasma source. Programmable heating and process controls contribute to the systems' unparalleled process flexibility.



Features

- Enhanced reliability, serviceability and performance
- 75-200mm wafer capabilities
- Proven platform
- Platen and lamp heating for process flexibility
- Programmable process parameters
- High throughput, excellent uniformity
- Reliable endpoint detection
- Small footprint, low cost of ownership
- System performance matching
- Optional SMIF Indexer, AGV and robotic cassette loading
- Stand-alone or flush mount installation



SPEC is the licensed manufacturer of
GaSonics products by Novellus





Product Specifications

Process

Gas Flows O₂=1000 – 4000 sccm; N₂/H₂=100 – 1000 sccm; N₂=100 –500 sccm

Pressure 0.5->5.0 torr

Platen Temperature 100 – 300 degree Celcius

μwave Power 0 – 1200 watt at 2.45 GHz

Lamp Utilization 0-100% (1000 watts)

Throughput (1.2 μm blanket softbaked resist ashed to end point

Desum/ST 45-60WPH

Photoresist 45-60WPH

Implanted & Damaged 45-60WPH

Within a wafer ±5%

Wafer to wafer (average) ±5%

Ash Rate up to 3.5 m./min

System Matching 5% (1 sigma)

Mobile Ion Concentration 1E10/cm₂ - 1E11/cm₂

CV Shift ≤0.1 volt

Particle <0.02/cm₂, size of 0.2_μm

Reliability

MTBF ≥168 hr. (6 mo. After sign-off) 300 hr.goal (12mo. After sign-off)

MTBA ≥36 hr.

MTTR ≤3 hr. for 80% of all downs

MTTA <5 min.

UPTIME (SEMI E10-92 STD) 89-95% (Equip. Dependent Uptime; must meet specific support requirements)

89-95% (Equip. Dependent Uptime; must meet specific support requirements)

General Information

Substrate size 3-8 inch/75mm-200mm

Footprint 30" (762 mm) W x 38" (965mm) D x 58" (1473mm) H

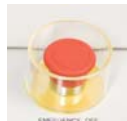
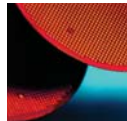
Electrical 200-240 VAC, 3 Phase, 50/60 Hz.
WYE configuration, 40 Amp. Breaker

Typical Process Gases O₂, N₂/H₂, N₂-regulated 18-23 PSIG

For Detail And Current Information Refer to:"L3510 Facility Inerface Matrix" – 17642-01

GaSonics L3510 Ashing System

150-200 Millimeter



Surplus Process
Equipment Corporation

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